

EUV scintillation in pure and xenon-doped liquid argon







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Xenon-doped liquid argon For particle detection

- Boiling temperature: 165 K
- Work function: $w_i = 15.6 \text{ eV}$
- ► Higher atomic mass (131 u) --> higher cross-section with WIMPs.
 - Very expensive, limited production.
 - Spin-dependent sensitivity.

- Boiling temperature: 87 K
- Work function: $w_i = 23.6 \text{ eV}$
- ³⁹Ar contamination ---> solved by using underground argon.

Ar

- Abundant --> higher scalability.
- Particle identification power.

Xenon-doped liquid argon For particle detection

- Boiling temperature: 165 K
- Work function: $w_i = 15.6 \text{ eV}$
- Xe Higher atomic mass (131 u) → higher cross-section with WIMPs.
 - Very expensive, limited production.
 - Spin-dependent sensitivity.



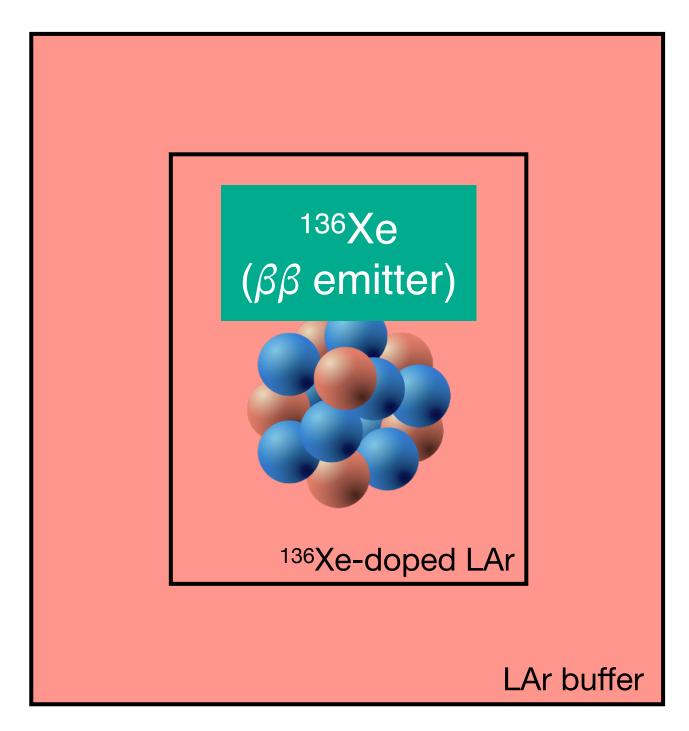
- **Higher light yield** for light dark matter search.
- **Better transparency** to improve photo-detection for large-scale detectors (DUNE).
- **Faster scintillation** for better timing resolution.

- Boiling temperature: 87 K Work function: $w_i = 23.6 \text{ eV}$ ³⁹Ar contamination ----> solved by using underground argon. Abundant --> higher scalability.
 - **Particle identification power.**

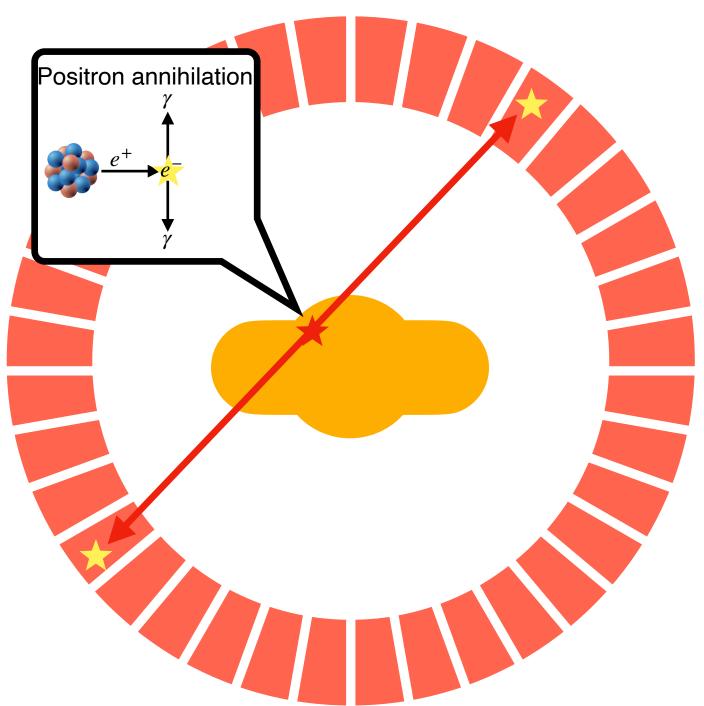
Xe+Ar

Example of applications of Xe-doped LAr Dark matter, neutrino physics, medical application

- Neutrinoless double beta-decay search with 136Xe-doped LAr.
- Smaller quantity of xenon required.
- Possibility to use a pure LAr outer veto.



- **Positron emission tomography** with Xe-doped LAr.
- Faster scintillation improves position reconstruction.
- With better resolution, the radioactive chemical dose can be reduced.





The X-ArT project **Xenon-Argon Technology**

The X-ArT program

- Xe-doping.
- ionization up to maximum solubility.



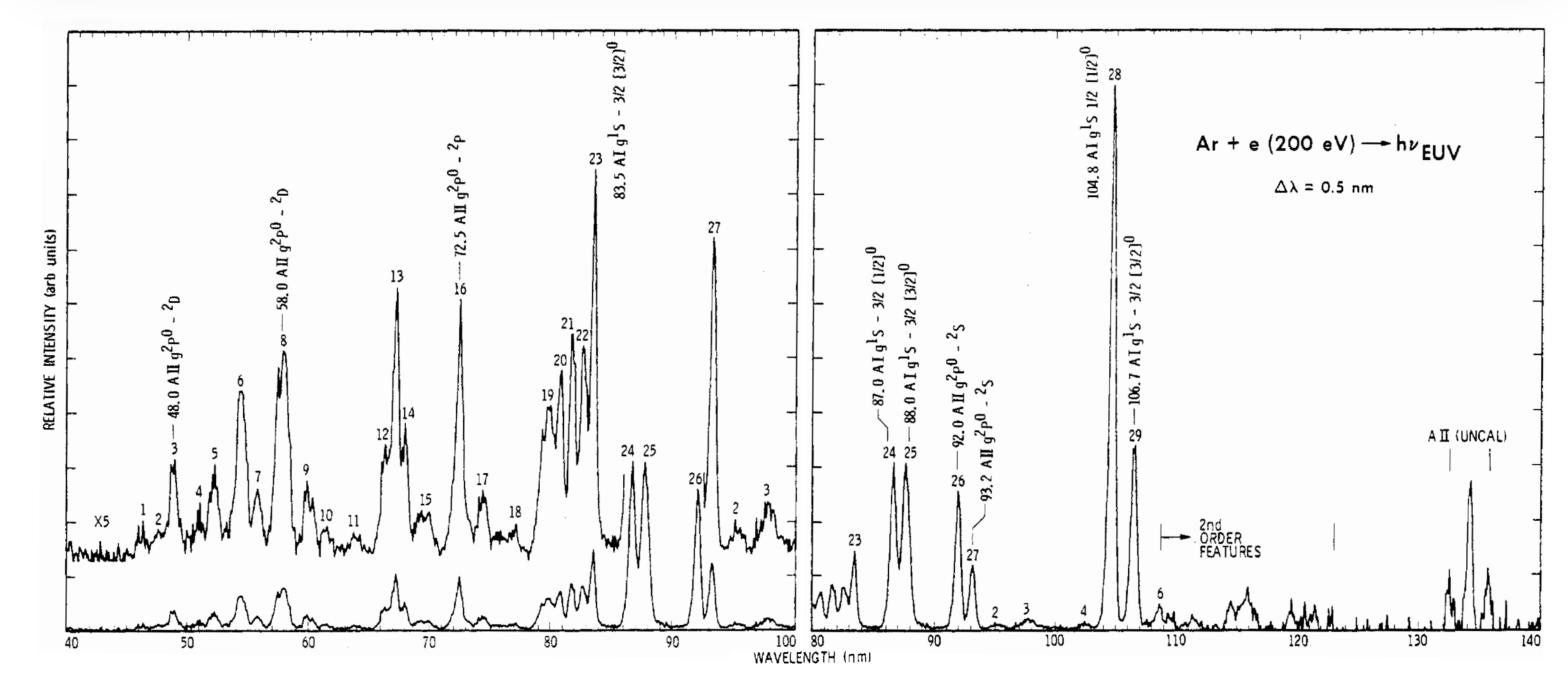
Determine the phase diagram of Xe+Ar.

Developing the **cryogenic** system enabling high

Characterising the **Xe-Ar scintillation and**

Scintillation study of pure and Xe-doped LAr Impact of extreme ultraviolet radiation

- scintillation.
- al 1990 J. Phys. B: At. Mol. Opt. Phys. 23 4355).



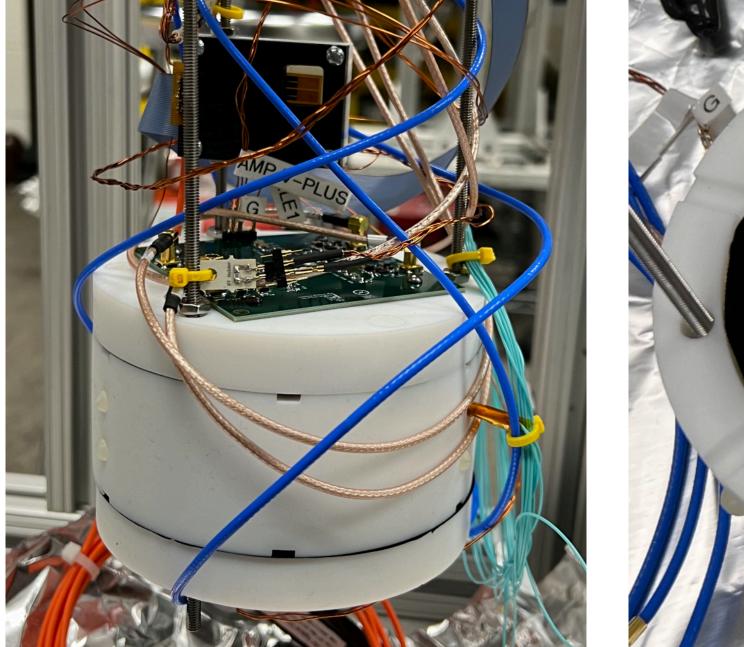
We show evidences of extreme ultraviolet (EUV) emission in LAr

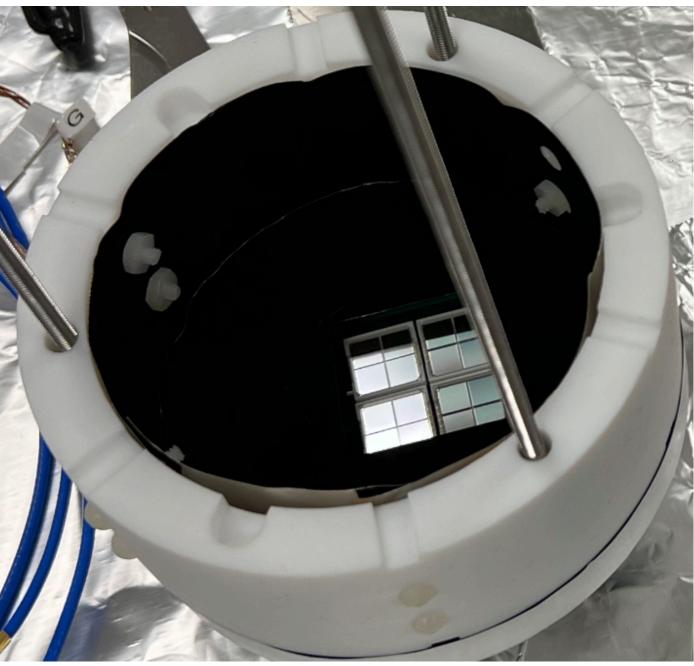
These emissions are attributed to **atomic state excitations** (*J. M. Ajello et*

The impact is a **long-lived (O(100 \mus)) component** in the scintillation pulse.



Single-phase chamber **Setup in Princeton**

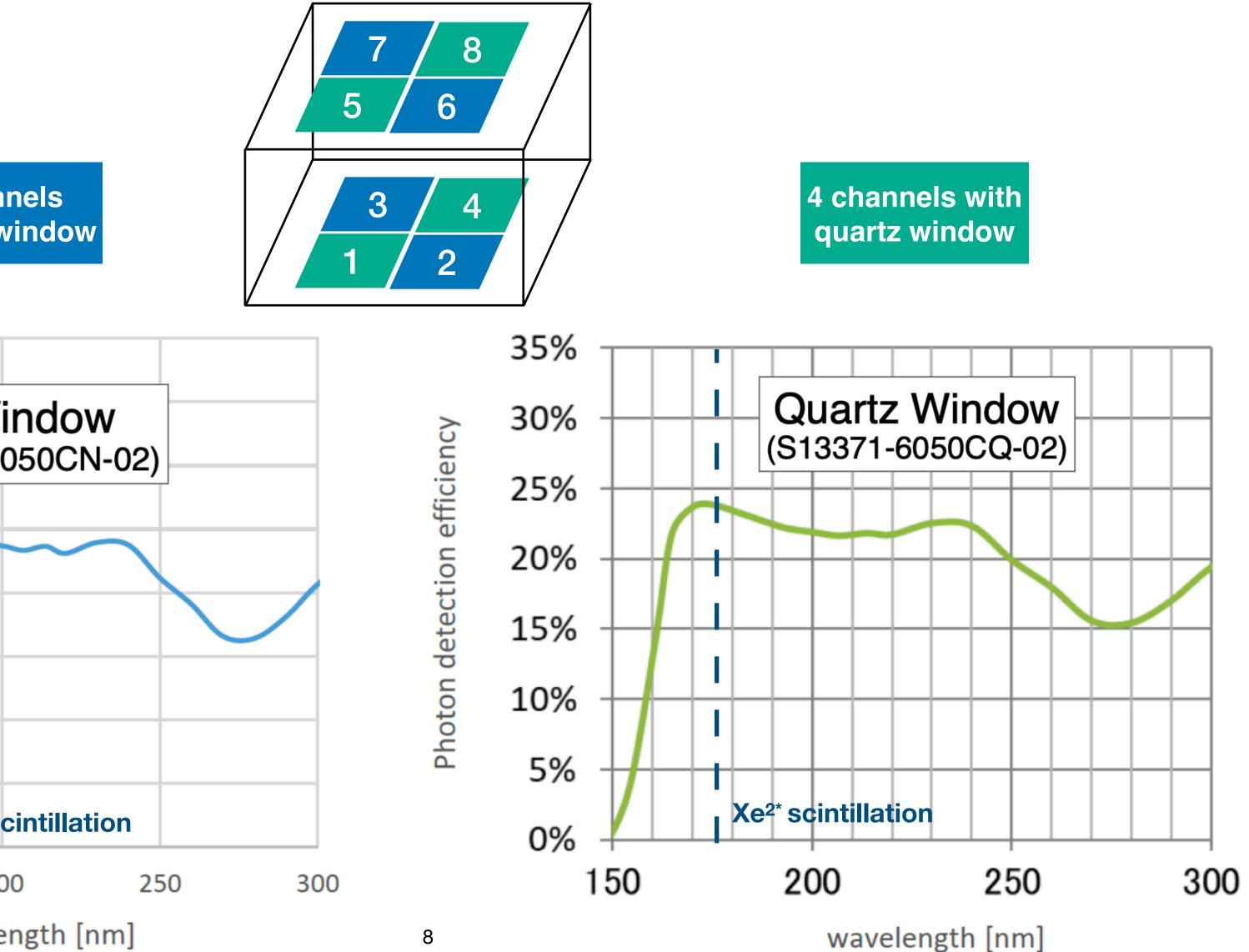


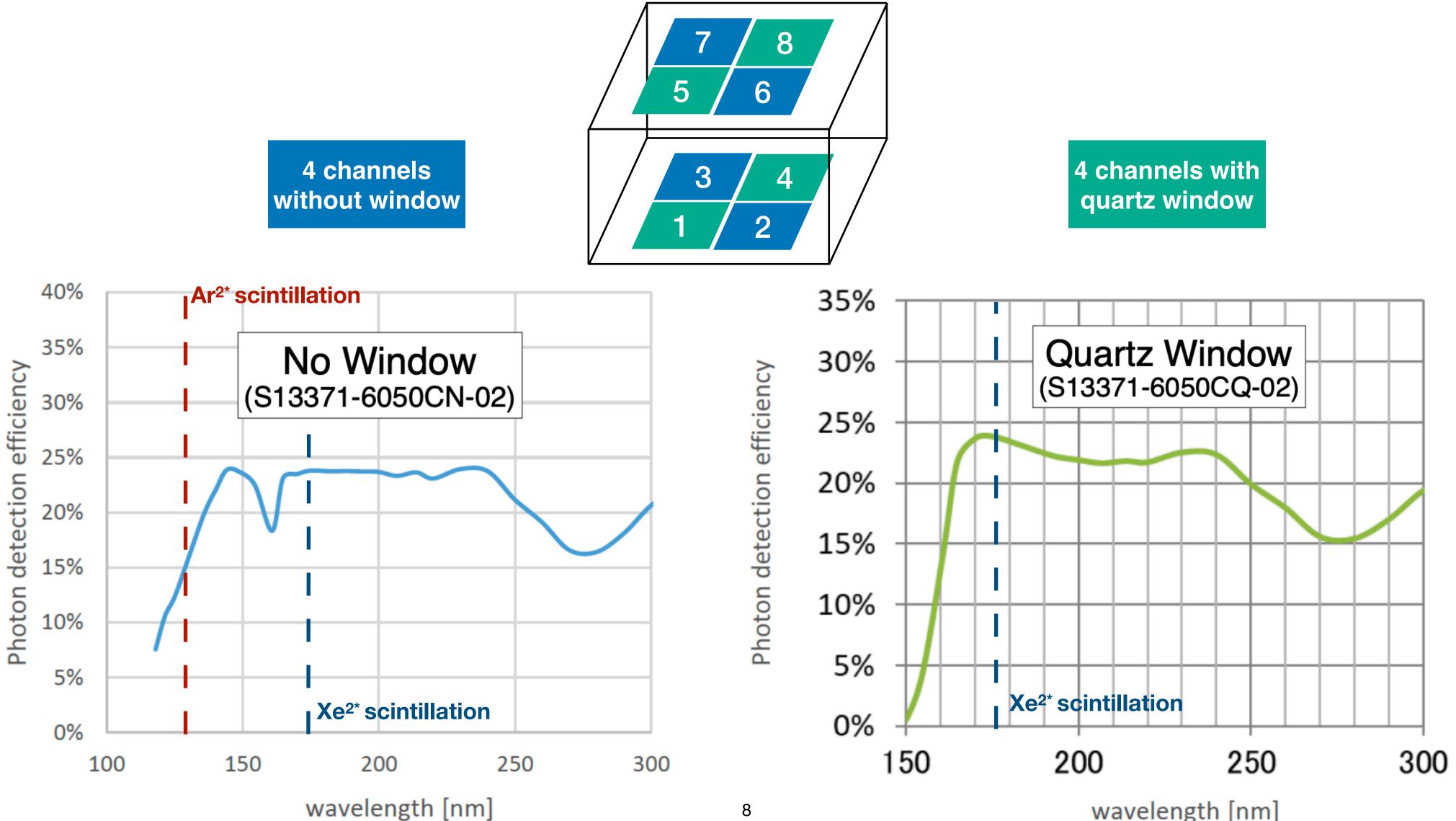




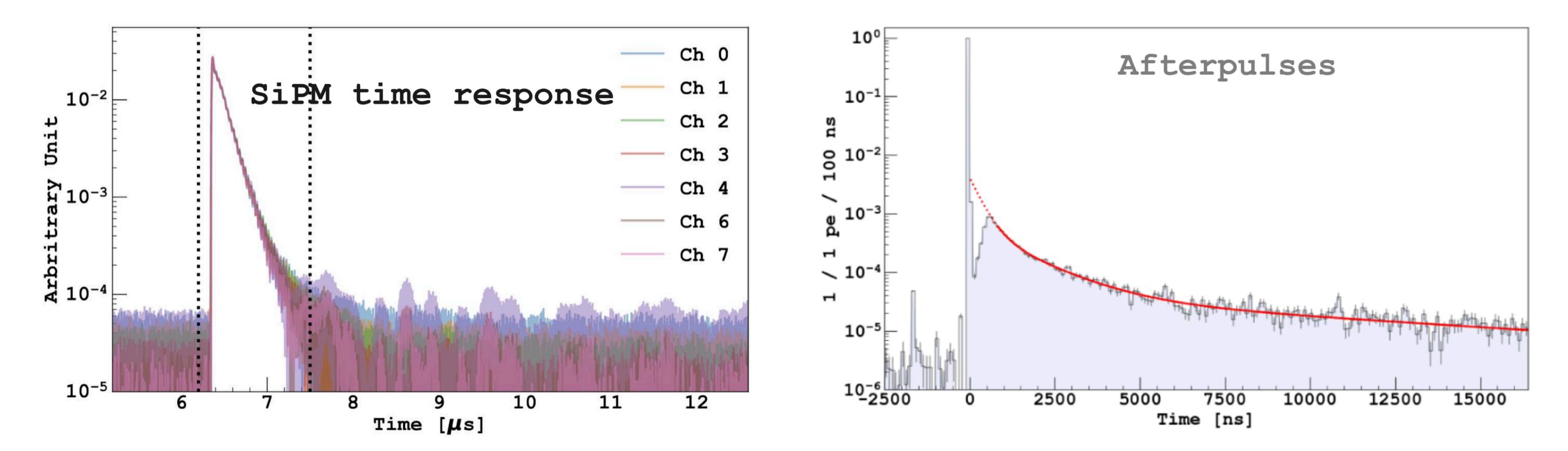
- Single-phase LAr chamber (4.5 cm height, 9.5 cm diameter)
- No reflectors, no wavelength shifter.
- Black absorbing foils.
- 8 SiPMs channels.
- Allows for xenon doping.

Windowed and windowless SiPMs For discrimination between Xe and Ar scintillations





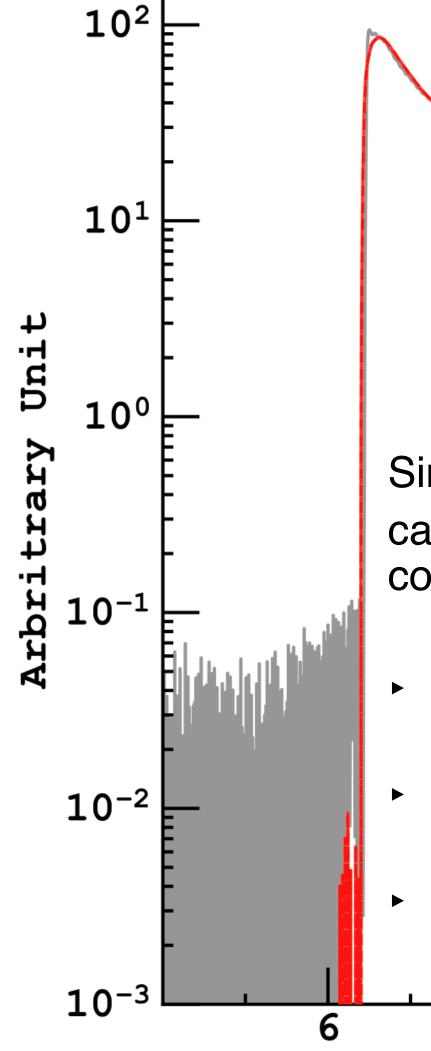
Laser calibration Single PE resolution and afterpulse characterisation

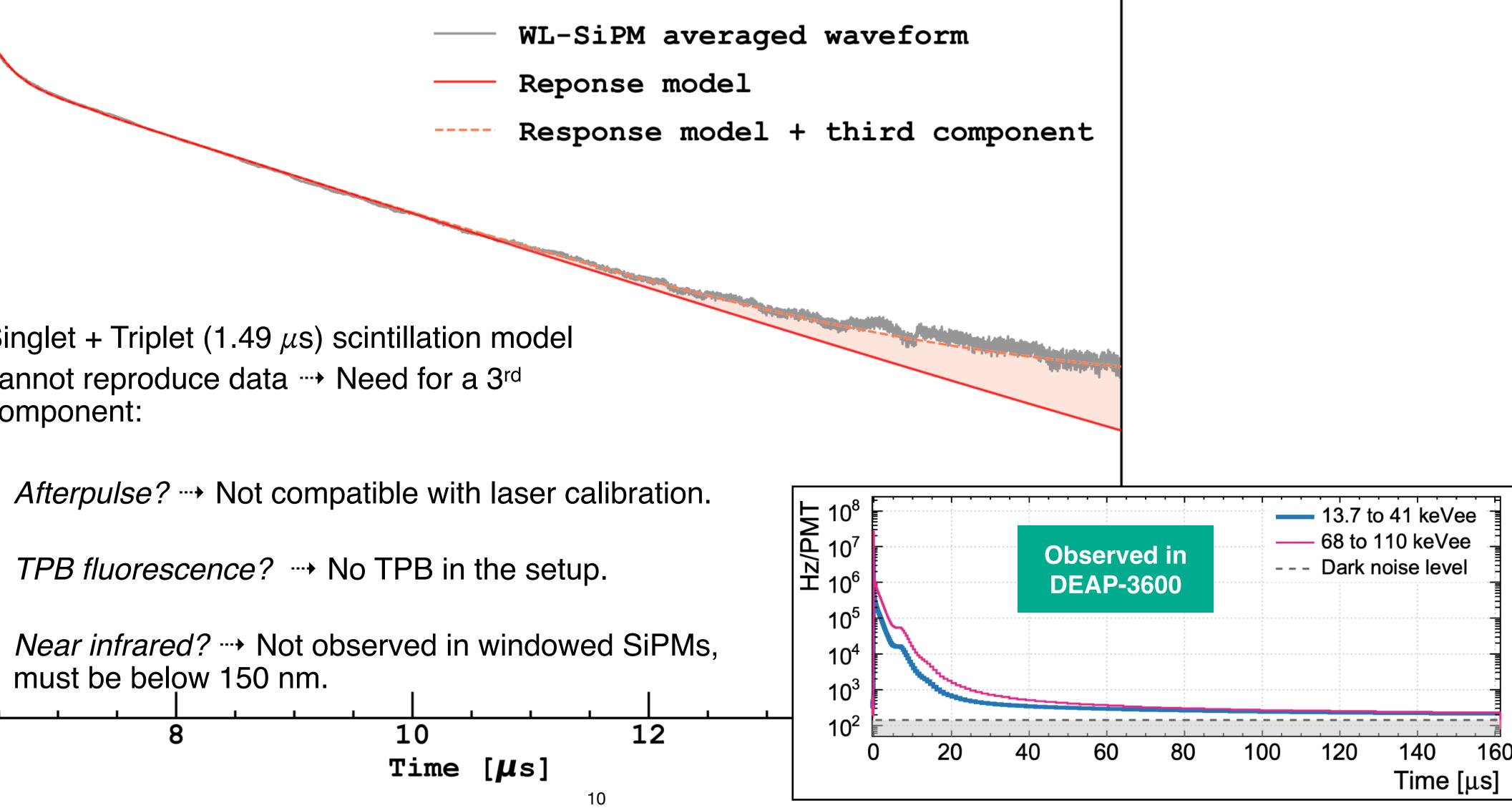


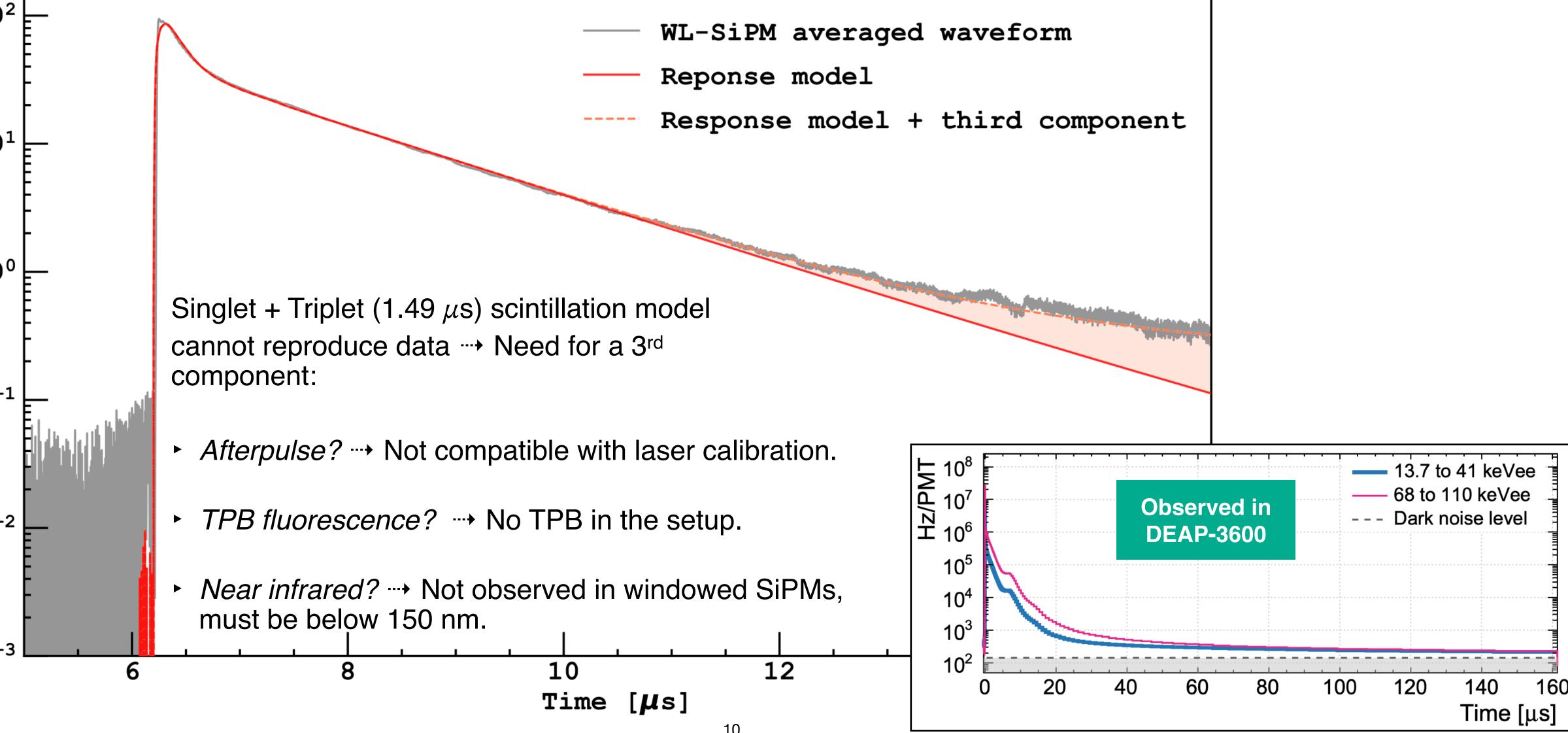
Afterpulse fitted with 3 exponential components:

Characteristic time	80 ± 13 ns	350 ± 30 ns	3010 ± 433 ns
Emission probability	26.8 ± 6.2 %	5.3 ± 0.4 %	1.4 ± 0.4 %

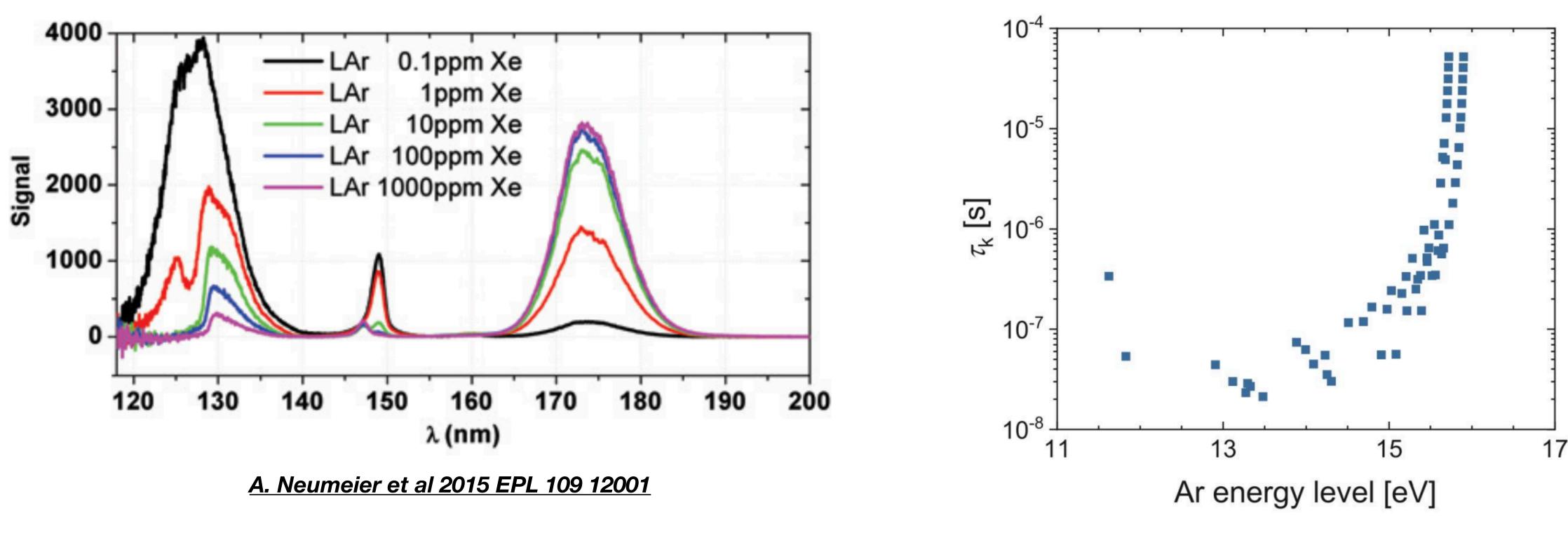
Observation of O(100 us) component In pure liquid argon, in window-less channels







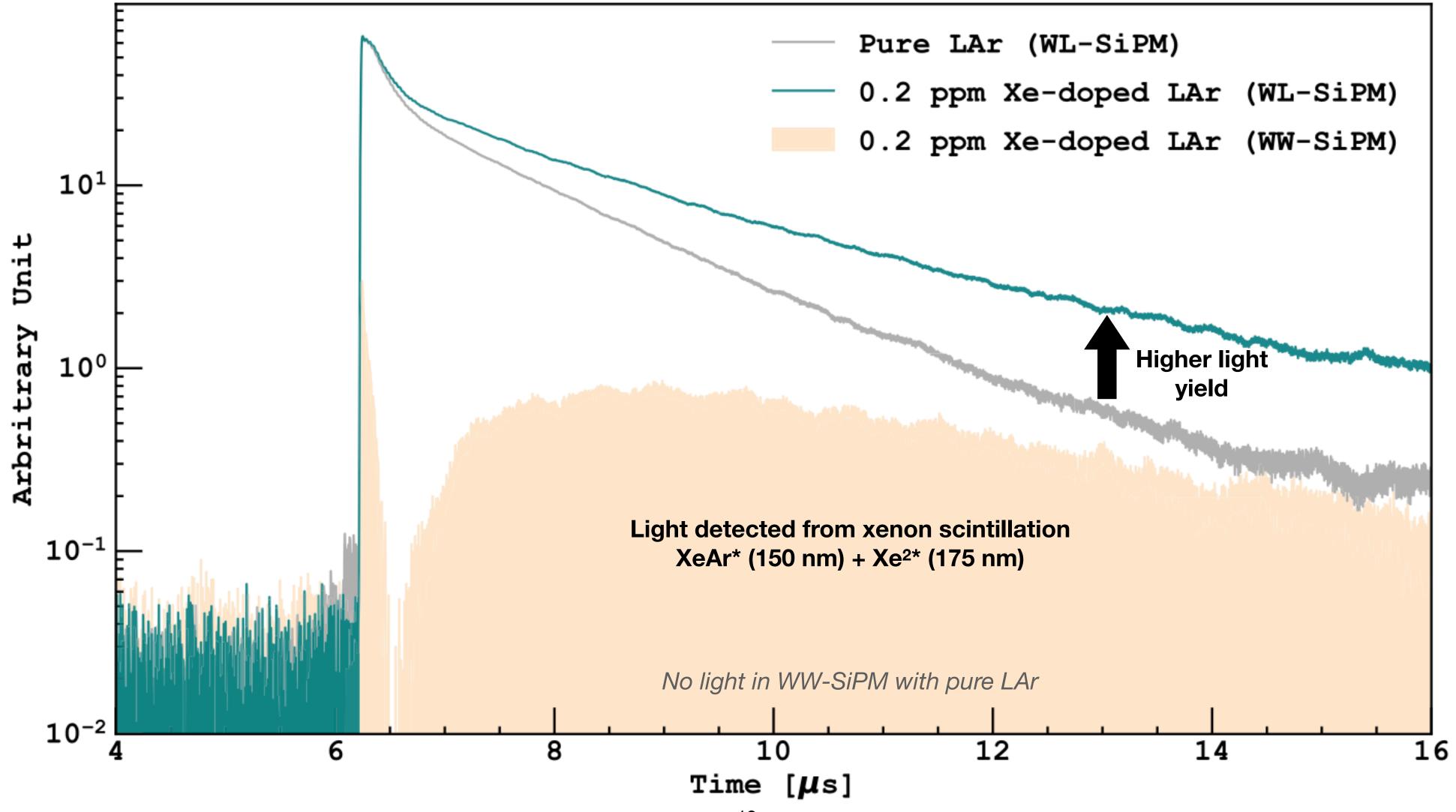
EUV emission in LAr Spectrum and characteristic times from atomic states



<u>10.1063/5.0071887</u>

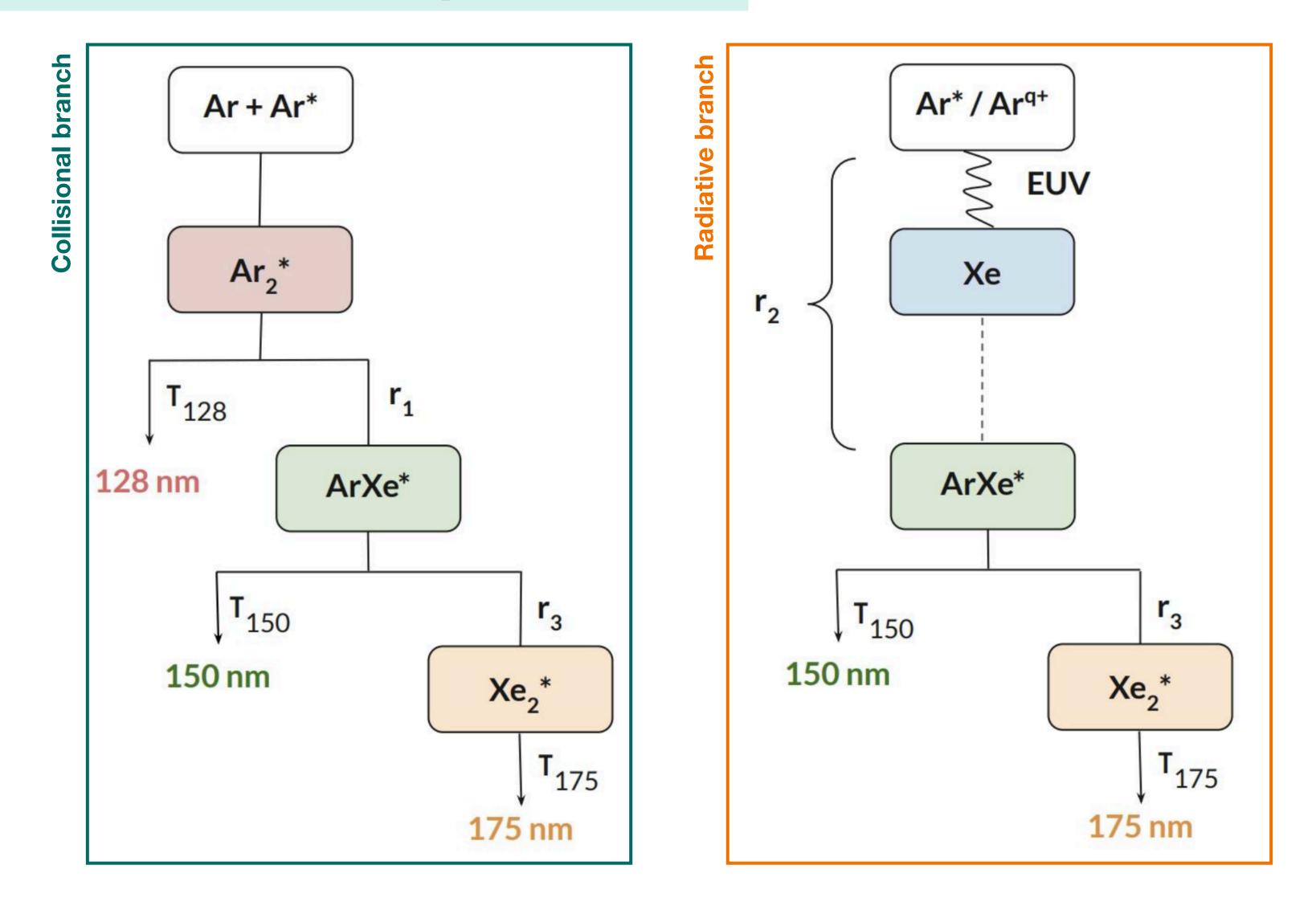
Xe-doped LAr

Increasing light yield and wavelength shifting

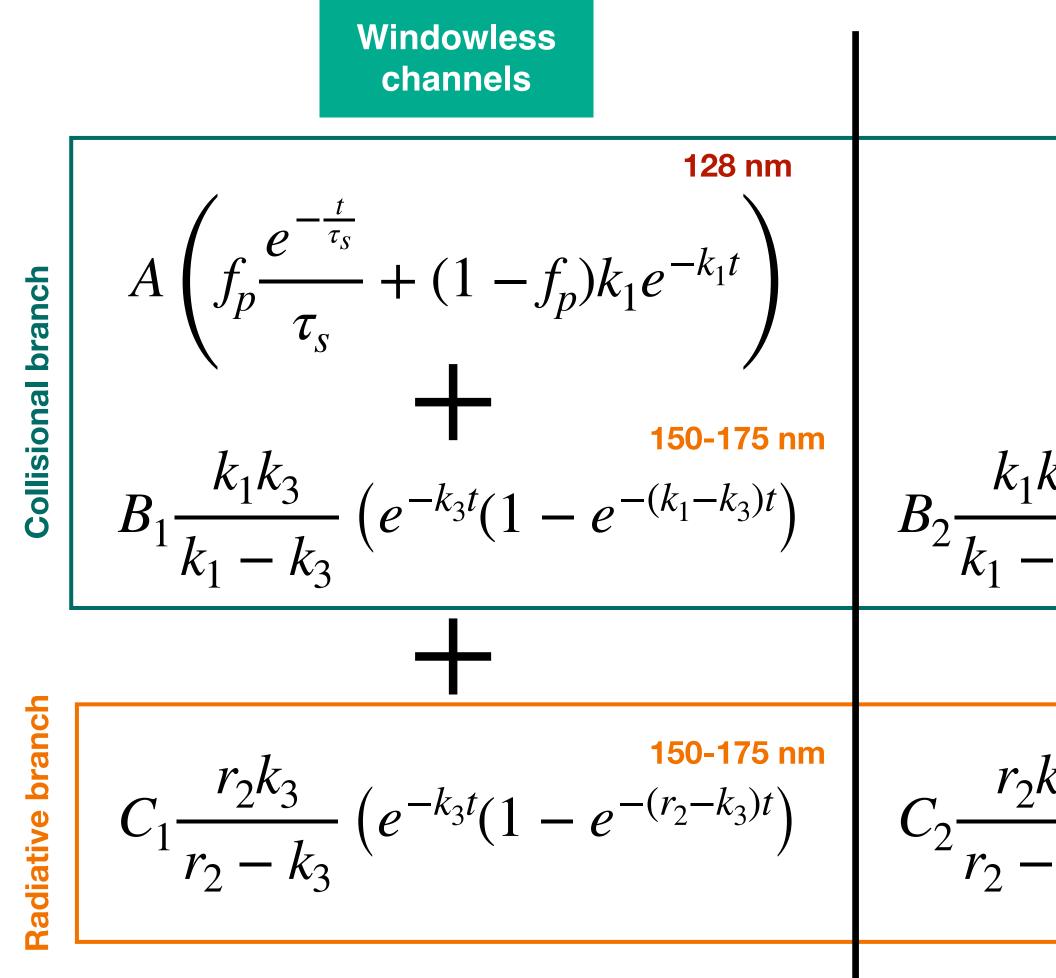


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Scintillation model for Xe-doped LAr Collisional and radiative processes



Scintillation model for Xe-doped LAr Analytical model



Windowed channels

$$\frac{k_3}{k_3} \left(e^{-k_3 t} (1 - e^{-(k_1 - k_3)t}) \right)$$

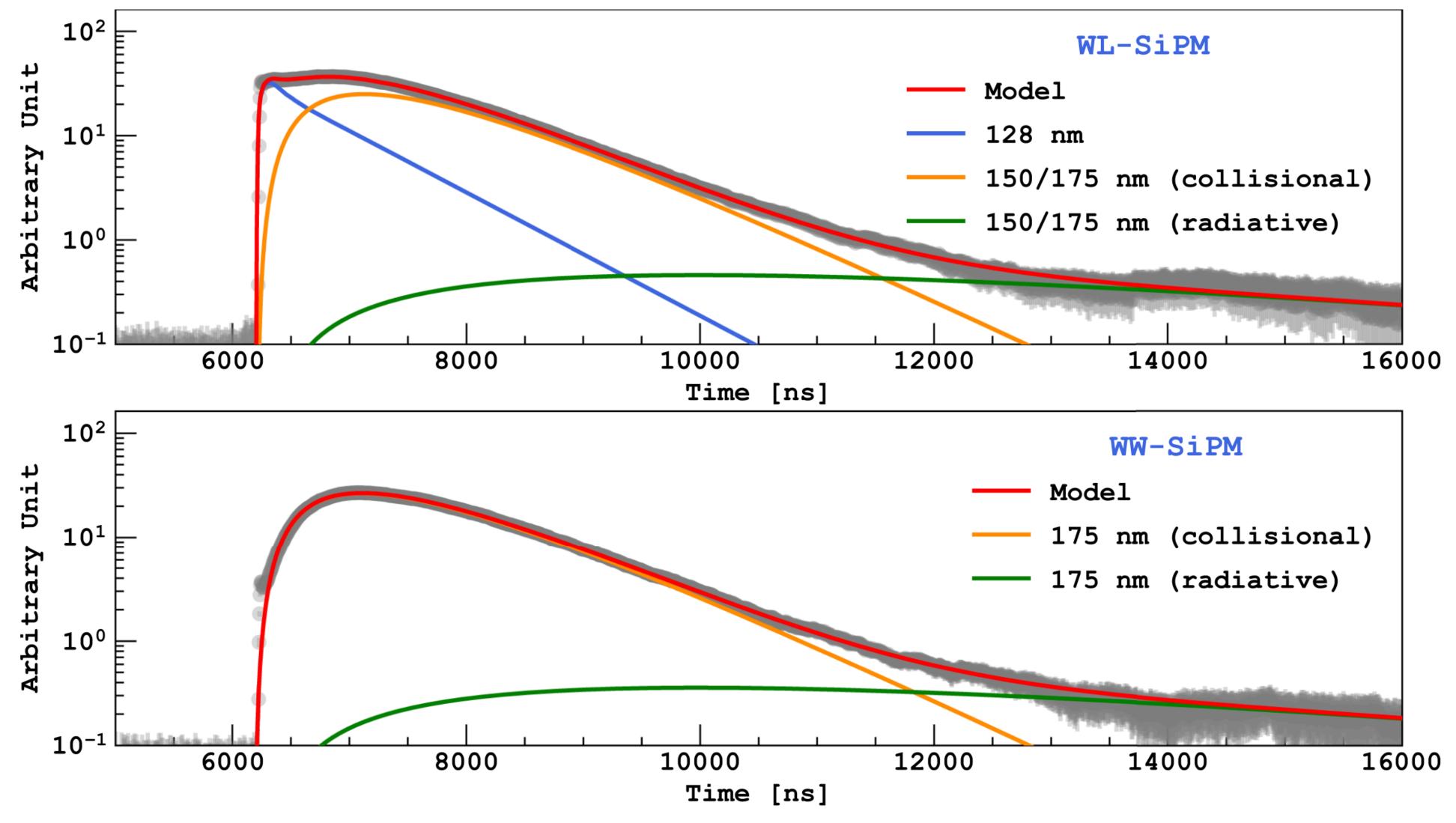
$$\frac{k_3}{k_3} \left(e^{-k_3 t} (1 - e^{-(r_2 - k_3)t}) \right)$$

• Ar^{2*}
$$\rightarrow$$
 ArXe* or \rightarrow 2Ar+128
 $k_1 = r_1 + \frac{1}{\tau_{128}}$

• ArXe*
$$\rightarrow$$
 Xe^{2*} or \rightarrow Ar+Xe+15
 $k_3 = r_3 + \frac{1}{\tau_{150}}$

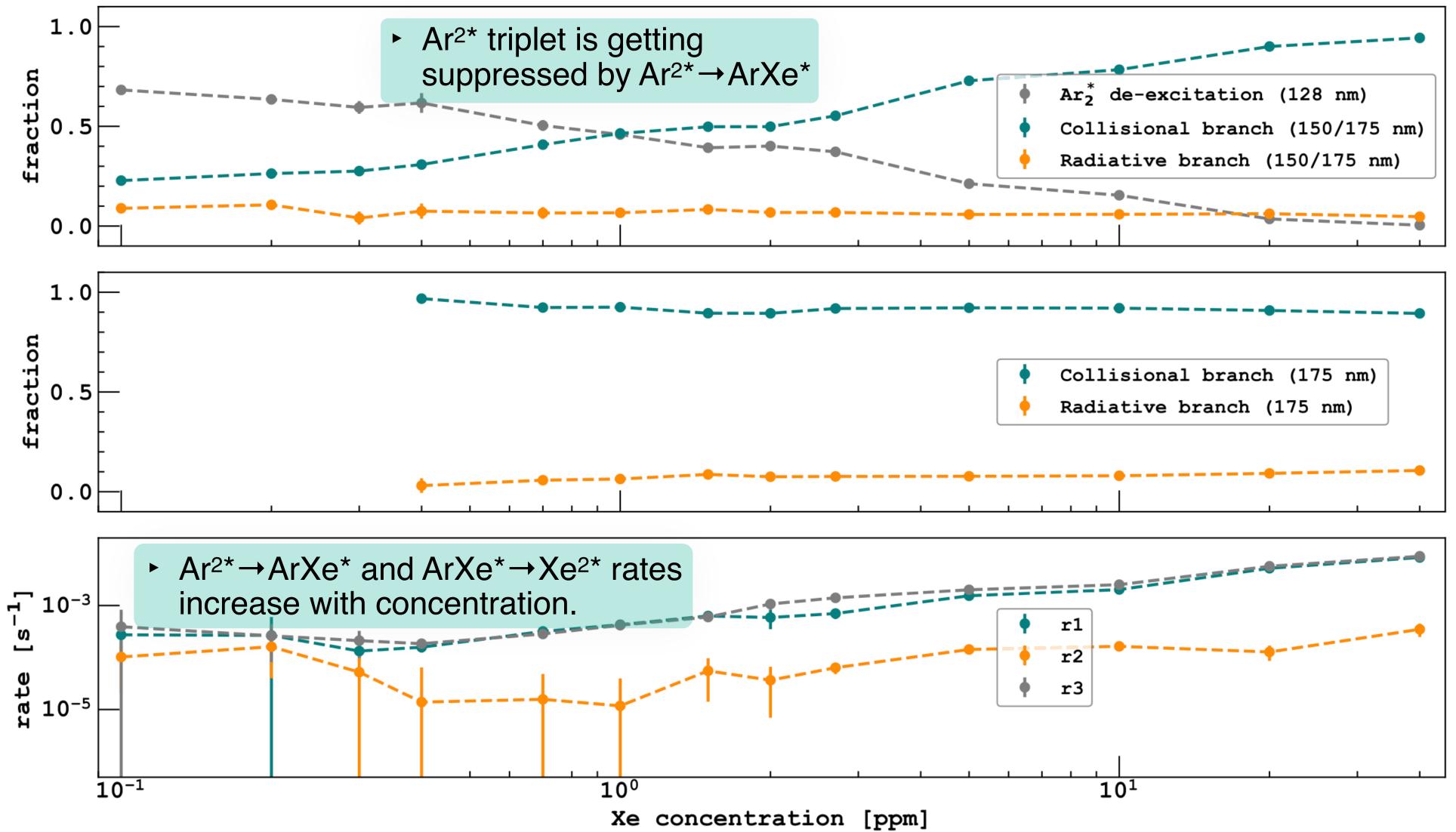
nm: 50 nm:

Model fit on summed waveforms Simultaneous fit of windowed and windowless channels



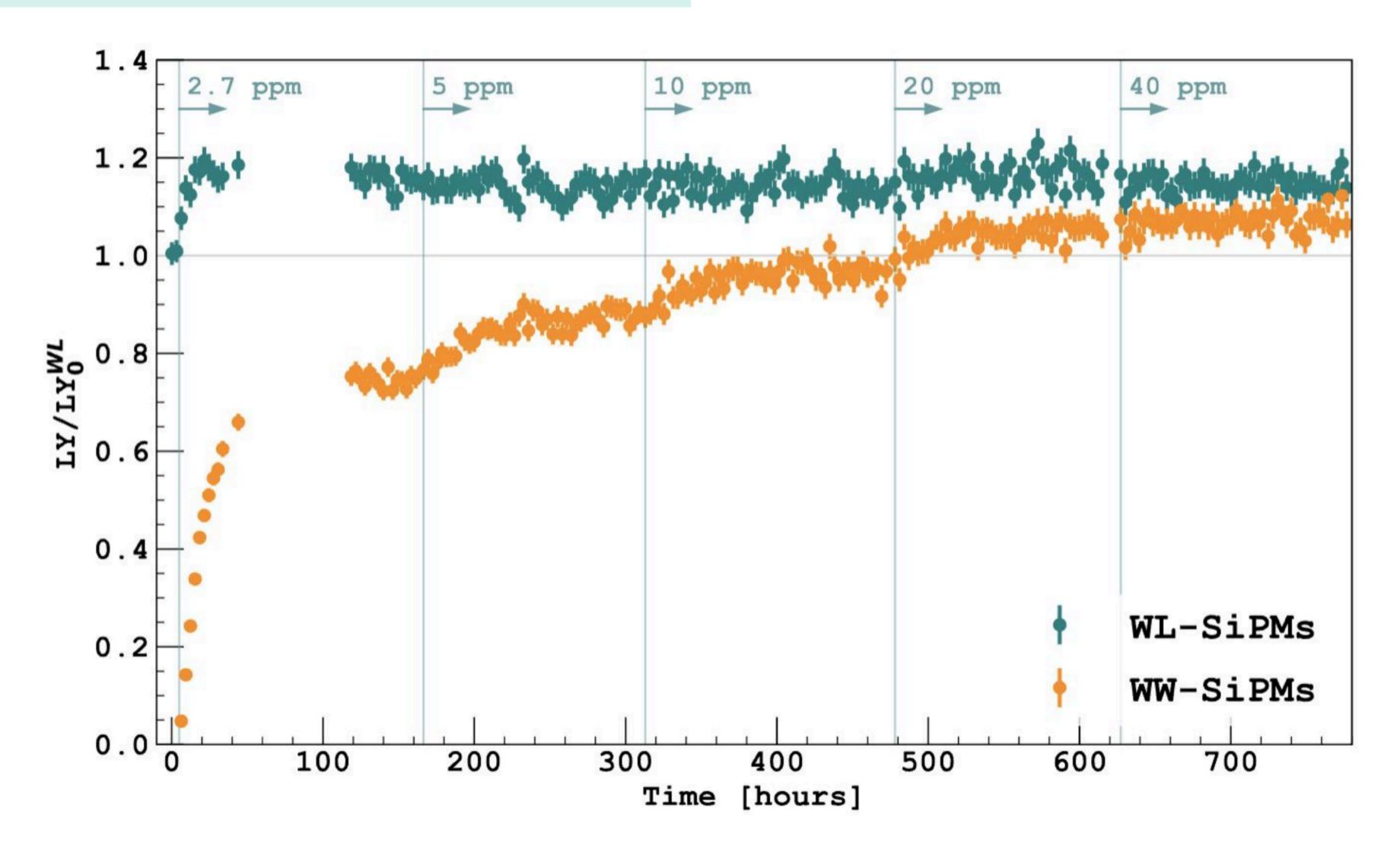
Fit of the summed waveforms

As a function of Xe concentration

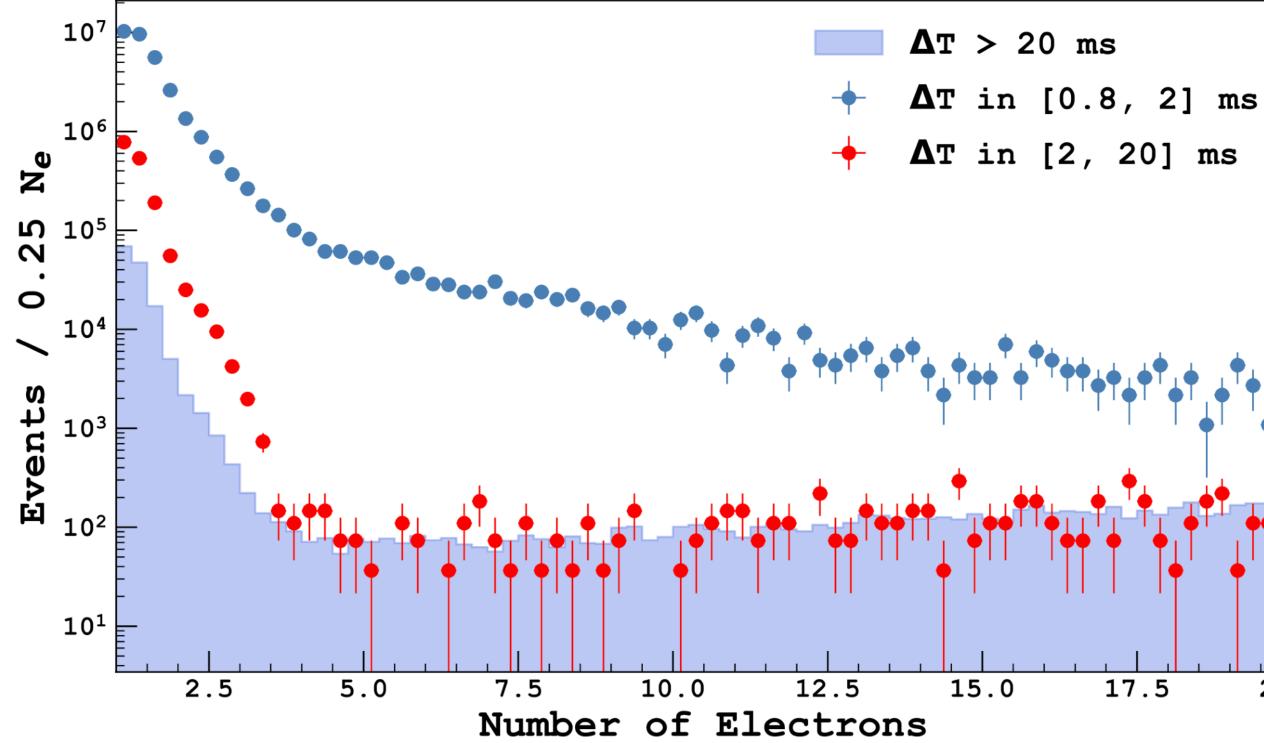


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Relative light yield Dependence on xenon-doping



A possible origin of the spurious electrons For the light dark matter search



- 20.0
- Excess at number of electrons from unclear origin, limiting the threshold for light dark matter analysis.
- Observed to be correlated with impurity level.
- **EUV** (expected to go up to 25 eV) could be the source of ionization of impurities.
- The multiplicity can increase from photo-ionization on the grid.

Impurity	O 2	CH ₄	Kr	CO ₂	H
Ionization energy	12.1 eV	12.6 eV	14.0 eV	13.8 eV	12.0



Ongoing and future measurements Within the X-ArT collaboration

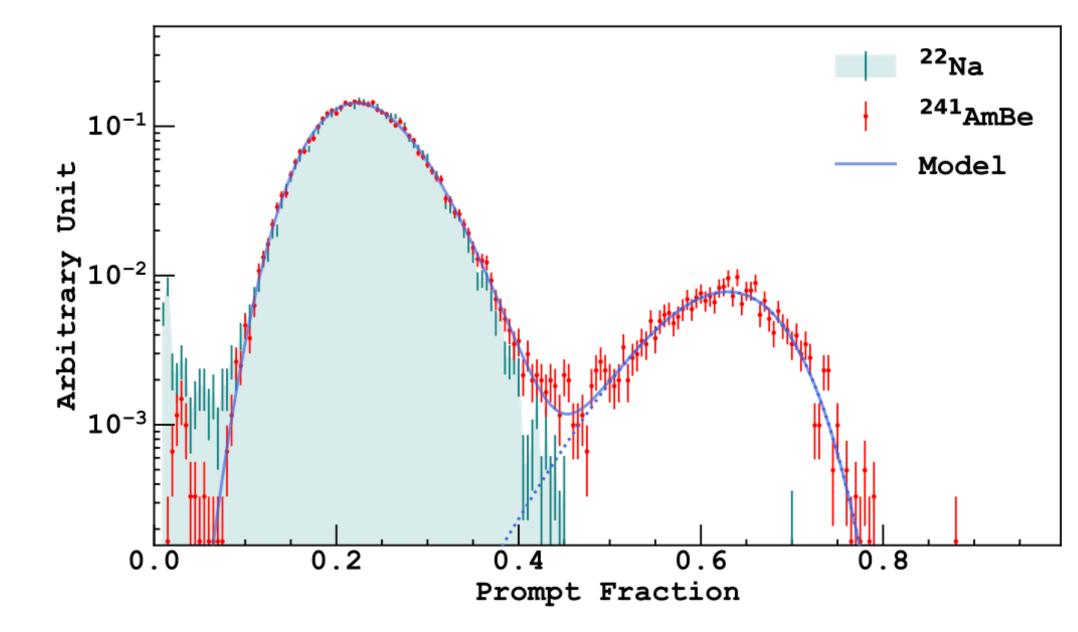
- We demonstrated the presence of long-lived EUV emission in LAr scintillation and proposed an explanation for the spurious electron background in light dark matter search.
- Data are being acquired with longer acquisition gate to fully characterise the long-lived component and the impact of Xe-doping on rise time.
- Preparation of a publication on the phase diagram of Xe+Ar (thermodynamics measurement and molecular simulation).
- Dual-phase setup for scintillation+ionization characterisation of xenon-doped LAr.

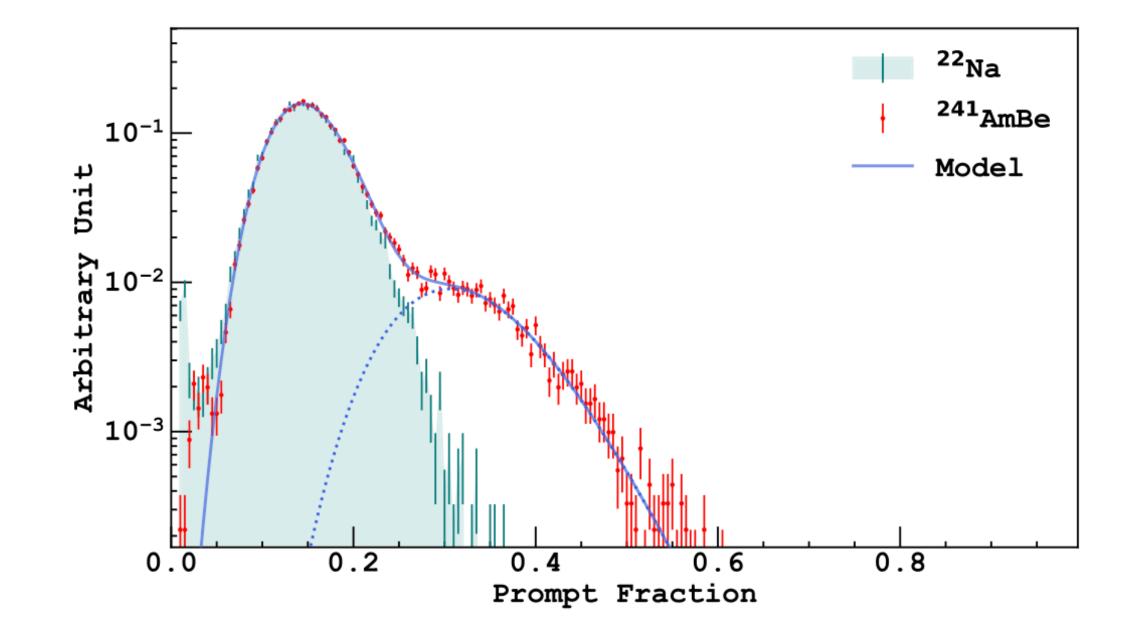
Thank you for your attention

BACK-UP SLIDES

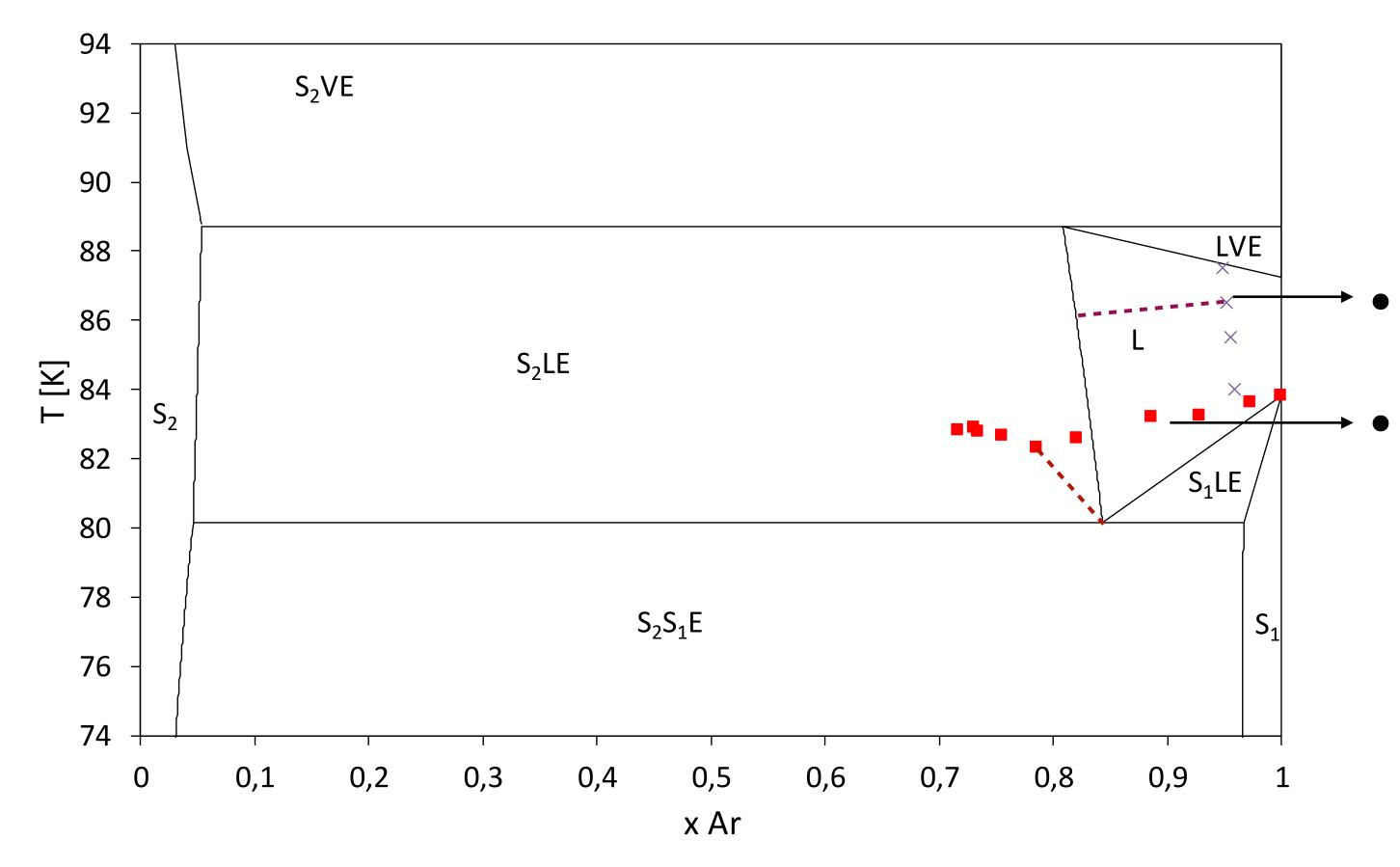


Pulse shape discrimination





Tension in measurement of xenon solubility



- Measured solubility: ~5%
- Measured solubility: ~20%

Phase diagram measurement

